



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Zhu et al.

Attorney Docket No.:
NOVLP090/NVLS-002888

Application No.: 10/733,858

Examiner: Not yet assigned

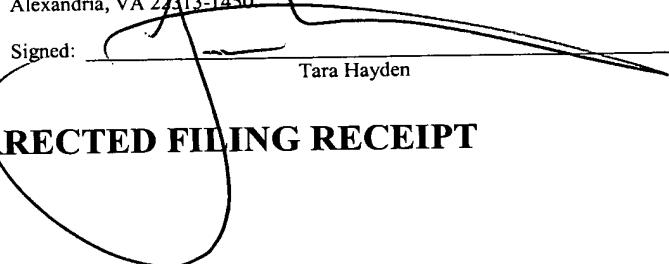
Filed: December 10, 2003

Group: 2812

Title: BIASED H₂ ETCH PROCESS IN
DEPOSITION-ETCH-DEPOSITION GAP
FILL

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as first-class mail on April 20, 2004 in an envelope addressed to the Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450

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REQUEST FOR CORRECTED FILING RECEIPT

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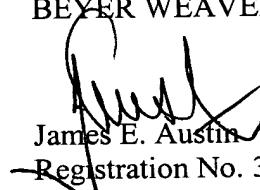
Sir:

Enclosed is a copy of the Filing Receipt for the above-identified patent application. Please reprint the Filing Receipt as follows and mail the corrected copy to the undersigned.

Change the Applicant "Pingsheng Sun" to --Pinsheng Sun--.

The Commissioner is authorized to charge any fees that may be due to Deposit Account 500388 (Order No. NOVLP090).

Respectfully submitted,
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APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY.DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/733,858	12/10/2003	2812	900	NOVLP090/NVLS002888	6	20	2



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CONFIRMATION NO. 7860
UPDATED FILING RECEIPT



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Date Mailed: 04/13/2004

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Assignment For Published Patent Application

Novellus Systems, Inc.;

Domestic Priority data as claimed by applicant
Foreign Applications

If Required, Foreign Filing License Granted: 03/17/2004

Projected Publication Date: Request for Non-Publication Acknowledged

Non-Publication Request: Yes

Early Publication Request: No



Title

Biased H2 etch process in deposition-etch-deposition gap fill

Preliminary Class

438

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Title 37, Code of Federal Regulations, 5.11 & 5.15**

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